

IN THE CLAIMS:

1. (Currently Amended) Photosensitive dispersion with adjustable viscosity for the deposition of metal on an insulating substrate, comprising, in combination, a powder conferring properties of oxidation-reduction under light irradiation, a metallic salt, a sequestering agent for the metallic salt, a liquid film-forming polymeric formulation selected from the group consisting of alkyl compounds, insoluble acrylic compounds, polyester compounds, epoxy compounds and acrylic emulsions, a basic compound, an organic solvent and water.
2. (Previously Presented) Dispersion according to Claim 1, wherein said powder is titanium dioxide.
3. (Previously Presented) Dispersion according to Claim 2, wherein the titanium oxide powder has a particle size of 10 nanometres to 10 micrometres.
4. (Previously Presented) Dispersion according to Claim 1, wherein the metallic salt is a transition metal salt.
5. (Previously Presented) Dispersion according to Claim 4, wherein the transition metal is selected from the group consisting of copper, gold, platinum, palladium, nickel, cobalt, silver, iron, zinc, cadmium, ruthenium and rhodium.

6. (Previously Presented) Dispersion according to Claim 5, wherein the transition metal salt is selected from the group consisting of copper (II) chloride, copper (II) sulphate, palladium (II) chloride, nickel (II) chloride and mixtures of at least two thereof.
7. (Previously Presented) Dispersion according to Claim 1, wherein the sequestering agent for the metallic salt is of the sulphate, chloride or carboxylic acid type.
8. (Previously Presented) Dispersion according to Claim 7, wherein the sequestering agent of the carboxylic acid type is tartaric acid, citric acid, a derivative of these or a mixture thereof.
9. (Previously Presented) Dispersion according to Claim 1, wherein the liquid film-forming polymeric formulation is a solution or emulsion.
10. (Cancel)
11. (Previously Presented) Dispersion according to Claim 1, wherein the basic compound is a base, a basic salt or a mixture thereof.
12. (Previously Presented) Dispersion according to Claim 11, wherein the basic compound is a base selected from the group consisting of potassium hydroxide, sodium hydroxide and ammonia.
13. (Previously Presented) Dispersion according to Claim 1, wherein the organic solvent is selected from the group consisting of ethers, esters, ketones, alcohols and mixtures thereof.

14. (Previously Presented) Dispersion according to Claim 13, wherein the organic solvent is selected from the group consisting of dioxane, cyclohexanone, 2-methoxy-1-methylethyl acetate, a mixture of dipropylene glycol methyl ether isomers, a mixture of tripropylene glycol methyl ether isomers and mixtures of at least two thereof.
15. (Previously Presented) Dispersion according to Claim 1, comprising deionised water.
16. (Previously Presented) Dispersion according to Claim 1, including at least one wetting agent, a dispersing agent or a mixture thereof.
17. (Previously Presented) Dispersion according to Claim 2, wherein the concentration of titanium dioxide, as a percentage by weight, is 1% to 50%.
18. (Previously Presented) Dispersion according to Claim 1, wherein the concentration of metallic salt, as a percentage by weight, is 0.01% to 5%.
19. (Previously Presented) Dispersion according to Claim 1, wherein the concentration of sequestering agent, as a percentage by weight, is 0.01% to 10%.

20. (Previously Presented) Dispersion according to Claim 1, wherein the concentration of film-forming polymeric formulation, as a percentage by weight, is 1% to 50%.

21. (Previously Presented) Dispersion according to Claim 1, wherein the concentration of base, as a percentage by weight, is 0.01% to 5% .

22. (Previously Presented) Dispersion according to Claim 1, wherein the concentration of organic solvent, as a percentage by weight, is 0.1% to 55% and.

23. (Previously Presented) Dispersion according to Claim 1, wherein the concentration of water, as a percentage by weight, is 1% to 15%.

24. (Previously Presented) Method of depositing metal on the surface of an insulating substrate, using the photosensitive dispersion according to Claim 1, comprising the application of the said dispersion in the form of a film on the substrate, selectively or not, the drying of the film applied to the said substrate and irradiation by means of ultraviolet radiation and/or laser with a range of wavelengths between 190 and 450 nm and an energy between 25 mJ/cm² and 100 mJ/cm² until a layer of metal, selective or not, is obtained on the substrate.

25. (New) Dispersion according to claim 6, wherein said transition metal salt is copper (II) chloride.